

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S11	446401	"6228823" and alkaline and Bis or tris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 13:49
S12	4	"6228823" and alkaline and (Bis or tris)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 13:53
S13	0	"2,2 Bis-hydroxyethyl-iminotris-hydroxymethylmethan"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 13:55
S14	0	"2,2 Bis-hydroxyethyl-iminotris-hydroxymethylmethan"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 13:56
S15	0	"(2,2)Bis-hydroxyethyl-iminotris-hydroxymethylmethan"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 13:57
S16	0	"2,2-Bis-(hydroxyethyl)-(iminotris)-(hydroxymethyl)methan"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 14:00
S17	195	(iminotris)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:34
S18	12288	nitrilotriacetic adj acid	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 15:14
S19	7207	nitrilotriacetic adj acid and solution same (clean\$4 or wash \$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 15:15
S20	2056	nitrilotriacetic adj acid and solution same (clean\$4 or wash \$4) same (len or glass or ceramic or metal)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 15:16
S21	7	nitrilotriacetic adj acid and solution same (clean\$4 or wash \$4) same (len or glass or ceramic or metal) and iminotris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:38
S22	2	"20050042198"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 15:54

S23	1	"20050042198" and iminotris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 15:55
S24	1	"20050042198" and iminotris and ammonium	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 15:57
S25	1	"20050042198" and iminotris and ammonium and hydroxide	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:23
S26	2	"20040120916"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:23
S27	0	"20040120916" and hydrogen adj peroxide	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:24
S28	0	"20040120916" and imonotris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:24
S29	1	"20040120916" and iminotris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:24
S30	555	len same solution and ammonium near5 hydroxide	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:39
S31	0	S30 and nitriloacetic adj acid	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:39
S32	13	S30 and nitrilotriacetic adj acid	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:41
S33	85856	(semiconductor or metal or conductor) same (solution or composition) same (clean\$4 or cleans\$4 or wash\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:43
S34	17	S33 and iminotris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:48
S35	10641	(semiconductor or conductor) same clean\$4 same solution	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:49

S36	14	S33 and (ammonium near hydroxide)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:49
S37	8350	S33 and (ammonium near hydroxide)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:50
S38	3064	S37 and peroxide	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:50
S39	3018	S37 and peroxide and water	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:50
S40	283	S37 and peroxide and water and nitrilotriacetic	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:51
S41	1	S37 and peroxide and water and nitrilotriacetic and iminotris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:51
S42	283	S37 and peroxide and water and nitrilotriacetic	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 16:51
S43	194	S37 and peroxide and water and nitrilotriacetic and EDTA	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 17:19
S44	1	"6191085" and nitrilotriacetic	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 17:28
S45	0	"6191085" and iminotris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 17:28
S46	1	"6191085" and bis	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 17:42
S47	0	"6191085" and bis and tris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 17:28
S48	11	"6228823"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 17:43

S49	4	"6228823" and nitrilotriacetic	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 17:43
S50	0	"6228823" and nitrilotriacetic and iminotris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:56
S51	22	(iminotris) and (conductor or semiconductor)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:00
S52	106	(iminotris) and metal	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:00
S53	87	S52 not S51	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:06
S54	158	"5290361"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:58
S55	0	"5290361" and iminotris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:08
S56	8	"5290361" and buffer	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:09
S57	0	"5290361" and bis adj tris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:13
S58	12744	bis adj tris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:13
S59	528	(bis adj tris) and solution and semiconductor	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:23
S60	6760	(bis adj tris) and solution same (clean\$4 or cleans\$4 or wash\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:17
S61	3	(bis adj tris) and solution same (clean\$4 or cleans\$4 or wash\$4) and nitrilotriacetic	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:18

S62	155	(bis adj tris) and polishing	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:25
S63	155	(bis tris) and polishing	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:25
S64	0	"7138016" and iminotris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:57
S65	2	"7138016"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:58
S66	0	"7138016" and bis	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:58
S67	8	"5290361" and bis	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:58
S68	1	"5290361" and bis same tris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/09/18 18:58
S69	0	iminotris same buffer and (semiconductor or wafer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/10/01 08:32
S70	6	iminotris same buffer and (semiconductor or wafer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/10/01 08:32
S71	47	iminotris same buffer and (semiconductor or glass or wafer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/10/01 08:40
S72	33	(iminotris or bistris) same buffer and (semiconductor or wafer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2007/10/01 08:41
S73	2	"20040092106"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 14:45
S74	12	("20040092106" "5290361" "5962384" "6191085" "6228823" "6465403").PN.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 14:57

S75	14031	bis tris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 15:15
S76	611	bis tris and (NTA or nitrilotriacetic acid)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 15:16
S77	0	("2004/0092106").URPN.	USPAT	OR	OFF	2008/04/10 15:28
S78	0	("2004/0092106").URPN.	USPAT	OR	OFF	2008/04/10 15:28
S79	168	Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 15:34
S80	28	S79 and surface same (treat\$4 or clean\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 15:40
S81	283	bis tris and (NTA or nitrilotriacetic acid) and (clean\$4 or treat\$) same (surface or semiconductor)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 15:49
S82	9	"6228823"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 15:53
S83	28	("4239661" "4339340" "4507278" "5460747" "5466389" "5505873" "5527423" "5552556" "5651861" "5656097" "5705089" "5739096" "5885362" "5908509" "5950645" "6114298" "6143706" "6162778" "6228179" "6228823" "6267122" "6309560" "6323169" "6465403" "6498132" "6630433" "6699828" "6927176").PN. OR ("7235516").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/04/10 15:55
S84	222165	S83 and bis or tris	US-PGPUB; USPAT; USOCR	OR	OFF	2008/04/10 15:56
S85	12	S83 and (bis or tris)	US-PGPUB; USPAT; USOCR	OR	OFF	2008/04/10 15:56
S86	1	"5962384" and (bis or tris)	US-PGPUB; USPAT; USOCR	OR	OFF	2008/04/10 16:03
S87	3	"5962384" and (bis or tris)	US-PGPUB; USPAT; USOCR	OR	ON	2008/04/10 16:03
S88	38	"5290361" and (bis or tris)	US-PGPUB; USPAT; USOCR	OR	ON	2008/04/10 16:08

S89	11	"6465403" and (bis or tris)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/04/10 16:20
S90	0	darmstadt-\$Marc Borner.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:23
S91	0	darmstadt-Marc\$.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:23
S92	0	darmstadt-\$borner.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:24
S93	46	darmstadt\$.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:24
S94	0	darmstadt\$.in. and (bis or tris)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:25
S95	16	Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane and semiconductor	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:30
S96	0	("6911393").URPN.	USPAT	OR	OFF	2008/04/10 16:30
S97	0	WO9960448	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:33
S98	2	WO-9960448-\$.did.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:33
S99	0	WO-9960448-\$.did. and (bis or tris)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:34
S100	5	"2004041989"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:46
S101	1016	Bis Tris and (semiconductor or wafer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:48
S102	88	Bis Tris and (semiconductor or wafer) and clean\$4 same substrate	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:49

S103	64	Bis Tris and (semiconductor or wafer) same clean\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:59
S104	169	Bis Tris and (semiconductor or wafer) same (clean\$4 or treat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 16:59
S105	2	ep-1091395-\$.did.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 17:09
S106	3117	Bis Tris and surface same (treat\$ or clean\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 17:21
S107	3117	"Bis Tris" and surface same (treat\$ or clean\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 17:21
S108	43	"Bis Tris" and surface same (treat\$ or clean\$4) same semiconductor	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 17:21
S109	43	"Bis Tris" and surface same (treat\$ or clean\$4) same semiconductor	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	OR	ON	2008/04/10 17:23
S110	128	buffer same nitrogen same Bis near tris	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	OR	ON	2008/04/10 17:28
S111	0	buffer same nitrogen same Bis near tris and semiconductor	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	OR	ON	2008/04/10 17:28
S112	23	buffer same nitrogen same Bis near tris and surface same (clean\$4 or treat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	OR	ON	2008/04/10 17:29
S113	1	buffer same nitrogen same Bis near tris and surface same metal same (clean\$4 or treat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	OR	ON	2008/04/10 17:29
S114	23	buffer same nitrogen same Bis near tris and (surface or wafer) same (clean\$4 or treat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	OR	ON	2008/04/10 17:30
S115	611	bis tris and (NTA or nitrilotriacetic acid)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 17:39

S116	72	bis tris same (NTA or nitrilotriacetic acid)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 17:39
S117	29	bis tris same (NTA or nitrilotriacetic acid) same buffer	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 17:39
S118	61	bis tris same (NTA or nitrilotriacetic acid) and (clean\$4 or treat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 17:40
S119	1	bis tris same (NTA or nitrilotriacetic acid) and (clean\$4 or treat\$4) and semiconductor	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/10 17:40
S120	319	(Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-tris) and clean\$4 same solution	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 08:25
S121	31	(Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-tris) and clean\$4 same solution and (semiconductor or wafer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 08:26
S122	283	(Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-tris) and (nitrilotriacetic or NTA)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 08:32
S123	33	(Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-tris) and (nitrilotriacetic or NTA) and hydrogen peroxide and water	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 08:35
S124	27	(Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-tris) and (nitrilotriacetic or NTA) and hydrogen peroxide and water and alkaline	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 08:36
S125	1	(Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-tris) and (nitrilotriacetic or NTA) and hydrogen peroxide and water and alkaline and ammonium hydroxide	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 08:44
S126	20	(Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-tris) and (nitrilotriacetic or NTA) and hydrogen peroxide and water and alkaline and (ammonium hydroxide or ammonia)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 08:45
S127	18	(Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-tris) and (nitrilotriacetic or NTA) and hydrogen peroxide and water and alkaline and (ammonium hydroxide or ammonia) and organic	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 08:47

S128	9	"6228823"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 08:59
S129	0	"6228823" and (Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-Tris) and (nitrilotriacetic or NTA)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:01
S130	25589	"6228823" and (Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-Tris) or (nitrilotriacetic or NTA)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:01
S131	4	"6228823" and ((Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-Tris) or (nitrilotriacetic or NTA))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:01
S132	10	"5962384"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:04
S133	2	"5962384" and (Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or NTA or nitrilotriacetic acid)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:06
S134	0	"5962384" and ((Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane) and (NTA or nitrilotriacetic acid))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:06
S135	19	"6228823" or "5962384"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:07
S136	9	"6228823" or "5962384" and (Bis (2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-Tris)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:08
S137	0	("6228823" or "5962384") and (Bis (2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-Tris)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:16
S138	0	("6228823" or "5962384") and (Bis (2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-Tris) and buffer	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:17
S139	1	("6228823" or "5962384") and ((Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane or Bis-Tris) or buffer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:18
S140	1927	ophthalmic solution and (ammonia or ammonium hydroxide)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:28

S141	102	ophthalmic solution and (ammonia or ammonium hydroxide) and (nitrilotriacetic or NTA or Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:28
S142	44	ophthalmic solution and (ammonia or ammonium hydroxide) and (nitrilotriacetic or NTA or Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane) and hydrogen peroxide	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:29
S143	0	ophthalmic solution and (ammonia or ammonium hydroxide) and (nitrilotriacetic or NTA or Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane) and hydrogen peroxide and alkaline compound	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:58
S144	44	ophthalmic solution and (ammonia or ammonium hydroxide) and (nitrilotriacetic or NTA or Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane) and hydrogen peroxide and (ammonium hydroxide or ammonia)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 09:59
S145	44	ophthalmic solution and (ammonia or ammonium hydroxide) and (nitrilotriacetic or NTA or Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane) and hydrogen peroxide and (ammonia)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 10:04
S146	47	(ophthalmic or contact len) near solution and (nitrilotriacetic or NTA or Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane) and hydrogen peroxide and (ammonia or ammonium hydroxide)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 10:19
S147	3	S146 not S145	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 10:19
S148	234	(ophthalmic or contact len) near solution and (ammonia or ammonium hydroxide) same sodium hydroxide	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 10:22
S149	116	(ophthalmic or contact len) near solution and (ammonia or ammonium hydroxide) same sodium hydroxide same pH	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 10:23

S150	4107	(nitritotriacetic or NTA) and surface same clean\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 10:53
S151	1607	(nitritotriacetic or NTA) and surface same clean\$4 and hydrogen peroxide and (ammonia or ammonium hydroxide) and water	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 10:55
S152	3858	(Bis-tris or Bis(2-hydroxyethyl) iminotris(hydroxymethyl) methane)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 10:55
S153	4	S152 and S151	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 10:56
S154	4573	(nitritotriacetic or NTA) and hydrogen peroxide and (ammonia or ammonium hydroxide) and water	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 10:56
S155	24	S154 and S152	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 10:56
S156	20	S155 not S153	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 10:57
S157	3858	(Bis-Tris or Bis(2-hydroxyethyl) iminotris(hydroxymethyl) methane)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 11:07
S158	2792	(Bis-Tris or Bis(2-hydroxyethyl) iminotris(hydroxymethyl) methane) same buffer	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 11:07
S159	740	(Bis-Tris or Bis(2-hydroxyethyl) iminotris(hydroxymethyl) methane) same buffer and surface same (treat\$4 or clean\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 11:08
S160	80	(Bis-Tris or Bis(2-hydroxyethyl) iminotris(hydroxymethyl) methane) same buffer and surface same (treat\$4 or clean\$4) same (metal or semiconductor)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 11:09
S161	162	"5290361"	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 11:24
S162	0	"5290361" and (Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 11:24

S163	5	"423"/\$ cds. and (Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 11:40
S164	9	"5290361" and buffer	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 11:45
S165	0	"5962384" and buffer	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 11:55
S166	31	((clean\$4) same (substrate or semiconductor)) and (Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane) same buffer	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 12:24
S167	29164	(nitrilotriacetic or NTA or Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 12:26
S168	283	(nitrilotriacetic or NTA) and (Bis-Tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/11 12:27
S169	6	(Bis-tris or Bis(2-hydroxyethyl)iminotris(hydroxymethyl) methane) same buffer and semiconductor same clean\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 14:54
S170	8	(Bis-tris or Bis(2-hydroxyethyl)iminotris(hydroxymethyl) methane) and semiconductor same clean\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 14:56
S171	3861	(Bis-tris or Bis(2-hydroxyethyl)iminotris(hydroxymethyl) methane)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:02
S172	875	(Bis-tris or Bis(2-hydroxyethyl)iminotris(hydroxymethyl) methane) and clean\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:02
S173	140	(Bis-tris or Bis(2-hydroxyethyl)iminotris(hydroxymethyl) methane) and clean\$4 and hydrogen near peroxide	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:02
S174	8	(Bis-tris or Bis(2-hydroxyethyl)iminotris(hydroxymethyl) methane) and clean\$4 same (semiconductor or metal) and hydrogen near peroxide	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:03
S175	329	(Bis-tris or Bis(2-hydroxyethyl)iminotris(hydroxymethyl) methane) and clean\$4 same (solution or formulation)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:04

S176	203	(Bis-tris or Bis(2-hydroxyethyl)iminotris(hydroxymethyl)methane) and (semiconductor or wafer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:25
S177	7	"510"/\$.ccls. and (Bis-tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane) and (semiconductor or wafer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:27
S178	0	"134"/\$.ccls. and (Bis-tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane) and (semiconductor or wafer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:28
S179	14	(Bis-tris or Bis(2-hydroxyethyl)iminotris(hydroxymethyl)methane) and (semiconductor or wafer) same clean\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:28
S180	4	"438"/\$.ccls. and (Bis-tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane) and (semiconductor or wafer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:30
S181	6	"257"/\$.ccls. and (Bis-tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane) and (semiconductor or wafer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:31
S182	0	"510"/\$.ccls. and method same clean\$4 and (Bis-tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane) and (semiconductor or wafer)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:32
S183	0	"510"/\$.ccls. (NTA and (Bis-tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane)) and surface	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:33
S184	0	"510"/\$.ccls. and (NTA and (Bis-tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane)) and surface	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:33
S185	172	(NTA and (Bis-tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane)) and surface	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:34
S186	172	(NTA and (Bis-tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane)) and surface and method	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:34
S187	2	(NTA and (Bis-tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane)) and hard surface and method	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:34
S188	13	(NTA and (Bis-tris or Bis(2-hydroxyethyl)iminotris (hydroxymethyl)methane)) and surface same clean\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	ADJ	ON	2008/04/15 15:35

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